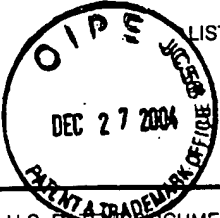


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2268	SERIAL NO. 10/822,118			
 <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT: Gurtej S. Sandhu et al.				
				FILING DATE April 8, 2004	GROUP 2812			
U.S. PATENT DOCUMENTS								
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
DV	AA	6,753,618	06/2004	Basceri et al.	257	915	—	
	AB	5,470,784	11/1995	Coleman	437	101	—	
	AC	2003/0219942 A1	11/2003	Choi et al.	438	253	—	
	AD	2004/0245560 A1	12/2004	Pontoh et al.	257	309	—	
	AE	2004/0245559 A1	12/2004	Pontoh et al.	257	306	—	
	AF	2004/0046197 A1	03/2004	Basceri et al.	257	296	—	
	AG	2004/0043228 A1	03/2004	Derderian et al.	428	446	—	
	AH	2003/0213987 A1	11/2003	Basceri et al.	257	296	—	
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EXAMINER <i>Shuland</i>		DATE CONSIDERED <i>12/03/05</i>						
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2268	SERIAL NO. 10/822,118		
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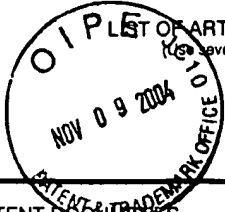
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↓	AB	6,350,560	02/2002	Sahbari	430	325	—
↓	AC	6,844,131	01/2005	Oberlander et al.	430	270.1	—
DV	AD	5,406,123	04/1995	Narayan	257	767	—
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FOREIGN PATENT DOCUMENTS								
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							Yes	No

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
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EXAMINER <i>Bruland</i>	DATE CONSIDERED <i>12/03/05</i>
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<div style="text-align: center;">  </div> <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT: Gurtej S. Sandhu et al.			
				FILING DATE April 8, 2004		GROUP 2812	
U.S. PATENT DOCUMENTS							
*Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
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U.S. PATENT DOCUMENTS								
Examiner's Initials	Class	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
DV	AA	3,349,474	12/1963	D. H. Rauscher				
	AB	5,904,517	05/1999	Gardner et al.	438	197		
	AC	5,998,264	12/1999	Wu	438	260		
	AD	6,180,465 B1	01/2001	Gardner et al.	438	291		
	AE	6,207,485 B1	03/2001	Gardner et al.	438	216		
	AF	6,548,854 B1	04/2003	Kizilyalli et al.	257	310		
	AG							
	AH	2003/0045060 A1	03/2003	Ahn et al.	438	287		
	AI	2003/0045078 A1	03/2003	Ahn et al.	438	585		
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DV	AJ	EP 0 851 473 A2	01/1998	EPO			X	
	AK							
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
DV	AM	Chang et al., Silicon surface treatments in advanced MOS gate processing, Microelectronic Engineering, (2004), pages 130-135						
DV	AN	Lemberger et al., Electrical characterization and reliability aspects of zirconium silicate films obtained from novel MOCVD precursors, Microelectronic Engineering (2004), pages 315-320						
DV	AO	Lu et al., Effects of the TaN _x interface layer on doped tantalum oxide high-k films, VACUUM (2004), pages 1-9						
EXAMINER <i>Richard</i>		DATE CONSIDERED 12/03/05						
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	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
DV	AM		Robertson et al., Atomic structure, band offsets, growth and defects at high-K oxide:Si interfaces, Microelectronic Engineering (2004) pages 112-120					
DV	AN		Singh et al., High and Low Dielectric Constant Materials, The Electrochemical Society <i>Interface</i> , Summer 1999, pages 26-30					
	AO							
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<div style="text-align: center;">  <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p> </div>				APPLICANT: Gurtej S. Sandhu et al.			
				FILING DATE April 8, 2004		GROUP 2812	
U.S. PATENT DOCUMENTS							
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DV	AA	4,086,074	04/78	Minot et al.			
	AB	4,693,910	09/87	Nakajima et al.			
	AC	4,766,090	08/88	Coquin et al.			
	AD	5,099,304	03/92	Takemura et al.			
	AE	5,670,298	09/97	Hur			
	AF	6,037,239	03/00	Jennings			
	AG	6,096,621	08/00	Jennings			
	AH	6,130,140	10/00	Gonzalez			
DV	AI	6,133,105	10/00	Chen et al.			
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
DV	AM	ABSTRACT: How to Eliminate Voiding in Porous-Low-k Dielectrics and The Mechanism of Void Formation; Lin et al.; 4 pages					
DV	AN	COB Stack DRAM Cell Technology beyond 100 nm Technology Node; Yongjik Park & Kinam Kim; pp. 349.1 - 349.3;					
	AO						
EXAMINER <i>Finland</i>		DATE CONSIDERED 12/03/05					
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Gurtej S. Sandhu et al.			
				FILING DATE April 8, 2004	GROUP 2812		
U.S. PATENT DOCUMENTS							
*Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
DV ↓	AA	6,133,116	10/00	Kim et al.	_____	_____	
	AB	6,156,674	12/00	Li et al.	_____	_____	
	AC	6,177,235 B1	01/01	Francou et al.	_____	_____	
	AD	6,277,709 B1	08/01	Wang et al.	_____	_____	
	AE	6,277,728 B1	08/01	Ahn et al.	_____	_____	
	AF	6,281,100 B1	08/01	Yin et al.	_____	_____	
	AG	6,291,363 B1	09/01	Yin et al.	_____	_____	
	AH	6,380,611 B1	04/02	Yin et al.	_____	_____	
DV	AI	6,383,723 B1	05/02	Iyer et al.	_____	_____	
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EXAMINER <i>Shuland</i>		DATE CONSIDERED 12/03/05					
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Gurtej S. Sandhu et al.			
				FILING DATE April 8, 2004		GROUP 2812	
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DV	AA	6,440,793 B1	08/02	Divakaruni et al.			
	AB	6,465,325 B2	10/02	Ridley et al.			
	AC	6,720,638 B2	04/04	Tran			
DV	AD	6,780,728	08/04	Tran			
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DV ↓ DV	AA	2001/0006759 A1	07/01	Shipley, Jr. et al.	—	—	—
	AB	2002/0076879 A1	06/02	Lee et al.	—	—	—
	AC	2002/0196651 A1	12/02	Weis	—	—	—
	AD	2003/0013272 A1	01/03	Hong et al.	—	—	—
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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EXAMINER <i>Simulard</i>		DATE CONSIDERED <i>12/03/05</i>					
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Gurtej S. Sandhu et al.			
				FILING DATE April 8, 2004		GROUP 2812	
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Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
DV	AA	10/609,311		Yates	—	—	06/03
DV	AB	10/655,997		Daley	—	—	09/03
DV	AC	10/879,367		Bialock et al.	—	—	06/04
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				FILING DATE April 8, 2004	GROUP Unknown			
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DV	AA	4,622,735	11/18/86	Shibata				
	AB	4,683,645	08/04/87	Naguib et al.				
	AC	5,236,865	08/17/93	Sandhu et al.				
	AD	5,444,024	08/22/95	Anjum et al.				
	AE	5,470,794	11/28/95	Anjum et al.				
	AF	10/689,958		Basceri			10/20/03	
DV	AG	10/690,029		Derderian et al.			10/20/03	
	AH							
FOREIGN PATENT DOCUMENTS								
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
DV	AK	ABSTRACT: Basceri et al., <i>Atomic Layer Deposition for Nanoscale CU Metalization</i> , 10 pages (pre-April 2004).						
DV	AL	En et al., <i>Plasma immersion ion implantation reactor design considerations for oxide charging</i> , 85 SURFACE AND COATINGS TECHNOLOGY 64-69 (1966).						
DV	AM	Ku et al., <i>The Application of Ion Beam Mixing, Doped Silicide, and Rapid Thermal Processing of Self-Aligned Silicide Technology</i> , 137 J. Electrochem. Soc. No. 2, pp. 728-740 (February 1990).						
DV	AO	Rubin et al., <i>Shallow-Junction Diode Formation by implantation of Arsenic and Boron Through Titanium-Silicide Films and ...</i> , 17 IEEE Transactions on Electron Devices, No. 1, pp. 183-190 (January 1990).						
EXAMINER <i>Brulem</i>		DATE CONSIDERED <i>12/03/05</i>						
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